

## **2025 Silicon Nanoelectronics Workshop 2025**

June 8<sup>th</sup>-9<sup>th</sup>, 2025

Rihga Royal Hotel, Kyoto, Japan

**Sunday, June 8<sup>th</sup>, 2025**

### **8:30 Opening remarks**

Kuniyuki Kakushima (Institute of Science Tokyo)

### **Session 1: Plenary Talks**

Session Chair: Kuniyuki Kakushima (Institute of Science Tokyo)

#### **8:40 1-01 (Plenary 1)**

##### **Amorphous Oxide Semiconductors for Memory Applications**

Hideo Hosono (Institute of Science Tokyo & National Institute of Materials Science, Japan)

#### **9:10 1-02 (Plenary 2)**

##### **Engineering High Quality Qubits in Silicon with Atomic Precision**

Michelle Y. Simmons (Silicon Quantum Computing & University of New South Wales, Australia)

**9:40-9:50 Break**

### **Session 2: Stacked Architecture and 3D Integration**

Session Chairs: Katsuhiko Tomioka (Hokkaido University) & Masaharu Kobayashi (The University of Tokyo)

#### **9:50 2-01 (Oral 1)**

##### **First Realization of ALD based Sn-Doped InGaZnO with Reliability Enhancements for Monolithic 3D Integration**

Sung-Hun Kim<sup>1</sup>, Sun Hong Choi<sup>1</sup>, Kota Sakai<sup>1</sup>, Takuya Saraya<sup>1</sup>, Toshiro Hiramoto<sup>1</sup>, and Masaharu Kobayashi<sup>1,2</sup> (<sup>1</sup>Institute of Industrial Science, The University of Tokyo, <sup>2</sup>d.lab, The University of Tokyo, Japan)

#### **10:10 2-02 (Oral 2)**

##### **Optimizing CFET Parasitic Capacitance and Performance Through Middle Dielectric Isolation and Middle Via Integration**

Meng-Lin Wu<sup>1</sup>, Yu-Cheng Lu<sup>2</sup>, and Vita Pi-Ho Hu<sup>1,2</sup> (<sup>1</sup>Graduate Institute of Electronics Engineering, National Taiwan University, <sup>2</sup>Graduate School of Advanced Technology, National Taiwan University, Taiwan)

#### **10:30 2-03 (Oral 3)**

### **Controlling phosphorus doping at the nanoscale to promote synthetic spin orbit coupling in silicon**

Michele Perego<sup>1</sup>, Stefano Kuschlan<sup>1</sup>, Francesc Perez-Murano<sup>2</sup>, Jordi Llobet<sup>2</sup>, Marta Fernandez-Regulez<sup>2</sup>, Riccardo Chiarcos<sup>3</sup>, Michele Laus<sup>3</sup>, Gabriele Seguini<sup>1</sup>, Andrea Pulici<sup>1</sup>, Graziella Tallarida<sup>1</sup> (<sup>1</sup>CNR-IMM, Unit of Agrate Brianza, Italy, <sup>2</sup>Institute of Microelectronics of Barcelona, Spain, <sup>3</sup>Università del Piemonte Orientale “A. Avogadro”, Italy)

**10:50-11:00 Break**

### **Session 3: Silicon Quantum Devices**

Session Chairs: Takahide Oya (Yohokama National University) & Pei-Wen Li (National Yang Ming Chiao Tung University (NYCU))

**11:00 3-01 (Invited 1)**

#### **Room Temperature Dopant-Atom Quantum Dot Transistors in Silicon**

Zahid Durrani<sup>1</sup> (<sup>1</sup>Imperial College London, UK)

**11:25 3-02 (Oral 4)**

#### **Experimental Demonstration of Vertically Stacked Parallel Silicon Quantum Dots**

Daiki Futagi<sup>1</sup>, Junoh Kim<sup>1</sup>, Tomoko Mizutani<sup>1</sup>, Takuya Saraya<sup>1</sup>, Hiroshi Oka<sup>2</sup>, Takahiro Mori<sup>2</sup>, Masaharu Kobayashi<sup>1,3</sup>, Toshiro Hiramoto<sup>1</sup> (<sup>1</sup>IIS, The Univ. of Tokyo, <sup>2</sup>AIST, <sup>3</sup>d.lab, The Univ. of Tokyo, Japan)

**11:45 3-03 (Oral 5)**

#### **Parallel Silicon Single-Electron Pumps for Generating Nanoampere Current**

Gento Yamahata<sup>1</sup>, Takase Shimizu<sup>1</sup>, Katsuhiko Nishiguchi<sup>1</sup>, Akira Fujiwara<sup>1</sup> (<sup>1</sup>NTT Basic Research Laboratories, Japan)

**12:05 3-04 (Oral 6)**

#### **High-Temperature Single-Electron Tunneling Through P-donors Affected by Confinement**

Pooja Sudha<sup>1</sup>, Soumya Chakraborty<sup>1</sup>, Daniel Moraru<sup>2</sup>, Arup Samanta<sup>1</sup> (<sup>1</sup>Indian Institute of Technology Roorkee (India), <sup>2</sup>Research Institute of Electronics, Shizuoka University, Japan)

**12:25-13:30 Lunch break**

### **Session 4: Advanced Logic and Memory Devices**

Session Chairs: Steve Chung (National Yang Ming Chiao Tung University (NYCU)) & Kasidit Toprasertpong (The University of Tokyo)

**13:30 4-01 (Invited 2)**

#### **High-Performance BEOL-Compatible ALD-IGZO Top-Gate Radio-Frequency Transistors**

Yanqing Wu<sup>1</sup>, Shenwu Zhu<sup>1</sup>, Qianlan Hu<sup>1</sup>, Anyu Tong<sup>1</sup> (Peking University, China)

**13:55 4-02 (Oral 7)**

**Vertical Channel Transistor-Based OS-Si Hybrid Gain Cell for High-Density and High-Retention Embedded DRAM**

Yu-Hsuan Chuang<sup>1</sup>, Vita Pi-Ho Hu<sup>1</sup> (<sup>1</sup>National Taiwan University, Taiwan)

**14:15 4-03 (Oral 8)**

**Below 10A CMOS-Double CFETs with Dielectric-wall-stress by Isolation-last Process for 0.0069  $\mu\text{m}^2$  of SRAM-cell Design**

Yi-Sung Chen<sup>2</sup>, Yu-Shang Shih<sup>2</sup>, Hao-Ming Huang<sup>2</sup>, Ting-Kuan Ma<sup>2</sup>, E Ray Hsieh<sup>1</sup> (<sup>1</sup>National Yang Ming Chiao Tung University, <sup>2</sup>National Central University, Taiwan)

**14:35 4-04 (Oral 9)**

**RRAM-Based In-Memory Stochastic Computing for Naïve Bayes Classifiers**

Haoran Wang<sup>1</sup>, Zongwei Wang<sup>1</sup>, Yabo Qin, Lin Bao, Yimao Cai<sup>1</sup> (<sup>1</sup>Peking Univ., China)

**14:55-15:05 Break**

**Session 5: Memory and Related Technologies**

Session Chairs: Minoru Oda (Kioxia) & Katsuhiko Nishiguchi (NTT Basic Research Laboratories)

**15:05 5-01 (Oral 10)**

**Observation of State Change in 40nm TaOX ReRAM Cells during Read-disturb**

Shota Suzuki<sup>1</sup>, Naoko Misawa<sup>1</sup>, Chihiro Matsui<sup>1</sup>, and Ken Takeuchi<sup>1</sup>

1Dept. of Electrical Engineering and Information Systems, The University of Tokyo, Japan

**15:25 5-02 (Oral 11)**

**Performance Evaluation of 3D 1T-nC Ferroelectric RAM Architectures**

Wei-Chen Chen<sup>1</sup>, Hang-Ting Lue<sup>1</sup>, Keh-Chung Wang<sup>1</sup>, and Chih-Yuan Lu<sup>1</sup> (<sup>1</sup>Macronix International Co., Ltd., Taiwan)

**15:45 5-03 (Oral 12)**

**Thermally Stable Vertical-Stacked 1T1C FeRAM with Record 3.3  $\mu\text{F}/\text{cm}^2$  CMW Based on Unified Ferroelectric-Oxide Semiconductor Stack**

Xujin Song<sup>1,2†</sup>, Dijiang Sun<sup>1,2†</sup>, Jiajia Zhang<sup>1,2</sup>, Chenxi Yu<sup>1,2</sup>, Xiaoyan Liu<sup>1,2</sup>, Jinfeng Kang<sup>1,2\*</sup> (<sup>1</sup>Peking University, <sup>2</sup>Beijing Advanced Innovation Center for Integrated Circuits, China)

**16:05 5-04 (Oral 13)**

**InAs/AlSb III-V NVM with High-speed (5ns) Low-power (1V) QW-tunnel Program for 10-year Storage by 2DEG-enhanced Retention**

Jun Sheng Hou<sup>1</sup>, Zi Yao Chung<sup>2</sup>, Min Jie Chen<sup>2</sup>, Ren Fu Ye<sup>1</sup>, Li Cheng Chen<sup>1</sup>, E Ray Hsieh<sup>3,\*</sup>, Jen-Inn Chyi<sup>1</sup> (<sup>1</sup>National Central Univ., <sup>2</sup>National Yang Ming Chiao Tung Univ., Taiwan)

**16:25 5-05 (Oral 14)**

**A Novel Cross-Point Ferroelectric-Capacitor Array based Parallel In-Memory Encryption for Energy-Efficient Secure-AI Applications**

Shengjie Cao<sup>1</sup>, Weikai Xu<sup>1</sup>, Zhiyuan Fu<sup>2</sup>, Minyue Deng<sup>1</sup>, Zebin Zhang<sup>1</sup>, Qianqian Huang<sup>1,3\*</sup> and Ru Huang<sup>1,3\*</sup> (<sup>1</sup>Peking University, China, <sup>2</sup>Southeast University, China, <sup>3</sup>Beijing Advanced Innovation Center for Integrated Circuits, China)

**16:45-17:00 Break**

**Session 6: Poster session with shot-gun presentations**

**17:00-18:30** Starting with short oral presentations (17:00~17:35)

Session Chairs: Daniel Moraru (Shizuoka University) & Katsuhiko Nishiguchi (NTT Basic Research Laboratories)

(List of posters is available at the end.)

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**Monday, June 9<sup>th</sup>, 2025**

**Session 7: Advanced Electronics on New Materials**

Session Chairs: Louis Hutin (CEA Leti) & Takahiro Shinada (Tohoku University)

**8:30 7-01 (Invited 3)**

**Capacitor-less IGZO based gain cell (2T0C): A disruptive technology for high-density eDRAM and 3D-DRAM**

Attilio Belmonte<sup>1</sup>, Hyungrock Oh<sup>1</sup>, Nouredine Rassoul<sup>1</sup>, Subhali Subhechha<sup>1</sup>, Adrian Chasin<sup>1</sup>, Daisuke Matsubayashi<sup>1</sup>, Yiqun Wan<sup>1</sup>, Harold Dekkers<sup>1</sup>, Romain Delhougne<sup>1</sup>, Gouri Sankar Kar<sup>1</sup> (<sup>1</sup>imec, Belgium)

**8:55 7-02 (Oral 15)**

**BEOL-Compatible IGZTO Thin-Film Transistors with Ultra-High Positive Bias Stress Stability for Advanced Electronics**

Kai Chen<sup>1,2</sup>, Xiaonan Wu<sup>1,2</sup>, Ran Cheng<sup>1</sup>, Rui Zhang<sup>1</sup>, Junkang Li<sup>1\*</sup>, Yunlong Li<sup>1,2\*</sup> (<sup>1</sup>Zhejiang University, China, <sup>2</sup>Zhejiang ICsprout Semiconductor Co., Ltd, China)

**9:15 7-03 (Oral 16)**

**Enhanced Electrical Characteristics of Ge MOS Device by In-situ Low Temperature H<sub>2</sub> Treatment**

Pai-Yu Hsiao<sup>1,†</sup>, Dun-Bao Ruan<sup>2,†</sup>, and Kuei-Shu Chang-Liao<sup>1\*</sup>, Hsin-I Yeh<sup>1</sup>, Chih-Wei Liu<sup>1</sup>, Yu-Hsuan Chien<sup>1</sup>, Bo-Lien Kuo<sup>1</sup>, Kai-Chun Yang<sup>1</sup>, Cheng-Han Li<sup>1</sup>, Cheng-Yu Wu<sup>1</sup> (<sup>1</sup>National Tsing Hua University, Taiwan, <sup>2</sup>Fuzhou University, China)

**9:35 7-04 (Oral 17)**

**Synergistic Impact of Random Phase Distribution and Polarization Strength Variations on FeFET Across Grain Sizes and Ferroelectric Percentages**

Yi-Ming Tseng<sup>1\*</sup> and Vita Pi-Ho Hu<sup>1,2\*\*</sup> (<sup>1</sup>National Taiwan University, Taiwan, <sup>2</sup>National Taiwan University, Taiwan)

**9:55 7-04 (Oral 18)**

**Unified Memcapacitor-Memristor Memory for Synaptic Weights and Neuron Temporal Dynamics**

S. D'Agostino<sup>1\*</sup>, M. Massarotto<sup>2\*</sup>, T. Torchet<sup>3</sup>, F. Moro<sup>3</sup>, N. Castellani<sup>1</sup>, L. Grenouillet<sup>1</sup>, Y. Beilliard<sup>1</sup>, D. Esseni<sup>2</sup>, M. Payvand<sup>3</sup>, and E. Vianello<sup>1†</sup> (<sup>1</sup>CEA, LETI, Universite Grenoble Alpes, France, <sup>2</sup>DPIA, Universita degli Studi di Udine, Italy, <sup>3</sup>University of Zurich and ETH Zurich, Switzerland)

**10:15 7-05 (Oral 19)**

**Poly-Si Nanosheet FETs With Vertical C-Shaped Channel Using Pulse Laser Crystallization**

Jinbiao Liu<sup>1</sup>, Zhuo Chen<sup>1</sup>, Yongkui Zhang<sup>1</sup>, Junfeng Li<sup>1</sup>, Xianglie Sun<sup>2</sup>, Shujuan Mao<sup>2</sup>, Guilei Wang<sup>2</sup>, Chao Zhao<sup>2</sup>, Huilong Zhu<sup>1</sup>, and Jun Luo<sup>1</sup> (<sup>1</sup>Institute of Microelectronics, Chinese Academy of Sciences, <sup>2</sup>Beijing Superstring Academy of Memory, China)

**10:35-10:45 Break**

**Session 8: Advanced CMOS Devices**

Session Chairs: Hiroaki Satoh (Shizuoka Univ.) & Runsheng Wang (Peking University)

**10:45 7-06 (Oral 20)**

**Heterojunction Tunneling and Reverse Shockley–Read–Hall Recombination Effects in Si<sub>1-x</sub>Ge<sub>x</sub> Channel/Si SDE CFETs for Steeper Subthreshold Swing and Low DIBL**

Pei-lun Chang, Ying-Tsan Tang\* (National Central University, Taiwan)

**11:05 8-02 (Oral 21)**

**Statistical Analysis of Subthreshold Current Distributions in bulk MOSFETs at Room and Cryogenic Temperatures**

Tomoko Mizutani<sup>1</sup>, Kiyoshi Takeuchi<sup>1</sup>, Takuya Saraya<sup>1</sup>, Hiroshi Oka<sup>2</sup>, Takahiro Mori<sup>2</sup>, Masaharu Kobayashi<sup>1</sup>, Toshiro Hiramoto<sup>1</sup> (<sup>1</sup>Univ. of Tokyo, <sup>2</sup>AIST, Japan)

**11:25 8-03 (Oral 22)**

**Investigation on Enhanced Hot Carrier Degradation in FinFETs at Cryogenic Temperature**

Zirui Wang<sup>1</sup>, Zuoyuan Dong<sup>1,2</sup>, Hongbo Wang<sup>1</sup>, Zixuan Sun<sup>1</sup>, Yue-Yang Liu<sup>3</sup>, Xing Wu<sup>2</sup>, Runsheng Wang<sup>1</sup> (<sup>1</sup>Peking Univ., <sup>2</sup>East China Normal Univ., <sup>3</sup>Inst. of Semiconductors, China)

**11:45 8-04 (Oral 23)**

**Study of Current Inflections in Reverse Bias in Nano-dimensional Silicon Esaki Diodes**

Daris Alfafa<sup>1,2</sup>, Arief Udhiarto<sup>2</sup>, Daniel Moraru<sup>1,3</sup> (<sup>1</sup>Graduate School of Sci. and Tech., Shizuoka Univ. (Japan), <sup>2</sup>Department of Electrical Eng., Univ. of Indonesia (Indonesia), <sup>3</sup>Res. Inst. of Electronics, Shizuoka Univ., Japan)

**12:05 8-05 (Oral 24)**

**Deep Learning to Automate Fitting and Parameter Extraction of 2D Transistors**

Robert K. A. Bennett<sup>1</sup>, Harmon F. Gault<sup>1</sup>, Asir Intisar Khan<sup>1</sup>, Lauren Hoang<sup>1</sup>, Tara Peña<sup>1</sup>, Kathryn Neilson<sup>1</sup>, Young Suh Song<sup>1</sup>, Zhepeng Zhang<sup>2</sup>, Andrew J. Mannix<sup>2</sup>, Eric Pop<sup>1,2,3</sup> (<sup>1</sup>Stanford Univ., Dept. of Electrical Eng., <sup>2</sup>Stanford Univ., Dept. of Materials Sci. & Eng., <sup>3</sup>Stanford Univ., Dept. of Appl. Phys., USA)

**12:25-13:30 Lunch break**

**Session 9: Interfaces and Reliability Engineering**

Session Chairs: Michele Perego (CNR-IMM) & Toshifumi Irisawa (AIST)

**13:30 9-01 (Invited 4)**

**Charge pumping electrically-detected magnetic resonance in Si MOS transistors — Identification of interface defects and dopant atoms —**

Masahiro Hori (Research Institute of Electronics, Shizuoka University, Japan)

**13:55 9-02 (Oral 25)**

**O/H Supercritical Fluid Passivation on Stacked Ge<sub>0.95</sub>Si<sub>0.05</sub> Nanosheet nFETs**

Min-Kuan Lin<sup>1</sup>, Ding-Wei Lin<sup>2</sup>, Jui-Yu Hsu<sup>2</sup>, Guan-Hua Chen<sup>2</sup>, Bo-Hui Yu<sup>3</sup>, Wei-Jen Chen<sup>2</sup>, Bo-Wei Huang<sup>2</sup>, Tao Chou<sup>1</sup>, Yi-Chun Liu<sup>2</sup>, Yu-Rui Chen<sup>2</sup>, Hong-Yi Tu<sup>4</sup>, Ting-Chang Chang<sup>5</sup>, and C. W. Liu<sup>1,2,3,\*</sup> (<sup>1</sup>Graduate School of Advanced Technology, <sup>2</sup>Graduate Institute of Electronics Engineering, <sup>3</sup>Graduate Institute of Photonics and Optoelectronics, National Taiwan University, Taipei, Taiwan, <sup>4</sup>Department of Materials and Optoelectronic Science, <sup>5</sup>Department of Physics, National Sun Yat-Sen University, Kaohsiung, Taiwan)

**14:15 9-03 (Oral 26)**

**Total Ionizing Doses Effects on MOSFET, FinFET, and GAAFET after Co-60 Radiation Exposure**

Jing-Lin Zheng<sup>1,†</sup>, Dun-Bao Ruan<sup>2,†</sup>, and Kuei-Shu Chang-Liao<sup>1,\*</sup>, Shang-Hua Hsu<sup>1</sup> (<sup>1</sup>National Tsing Hua University, Taiwan, <sup>2</sup>Fuzhou University, China)

**14:35 9-04 (Oral 27)**

**Improved Uniformity and Endurance of Ag-based Volatile Memristors via Annealing Engineering**

Yading Yi<sup>1,3</sup>, Xujin Song<sup>1,3</sup>, Zhuohua Tang<sup>1,3</sup>, Shangze Li<sup>1,3</sup>, Dijiang Sun<sup>1,3</sup>, Shiyue Song<sup>1,3</sup>, Yulin Feng<sup>\*2</sup>, Zheng Zhou<sup>1,3</sup>, Peng Huang<sup>1,3</sup>, Jinfeng Kang<sup>1,3</sup>, Lifeng Liu<sup>\*1,3</sup> (<sup>1</sup>Peking University; <sup>2</sup>Beijing Information Science and Technology University; <sup>3</sup>Beijing Advanced Innovation Center for Integrated Circuits, China)

**14:55-15:05 Break**

**Session 10: Quantum-Dot Devices**

Session Chairs: Gento Yamahata (NTT Basic Research Laboratories) & Daniel Moraru (Shizuoka University)

**15:05 10-01 (Invited 5)**

**Spatial Noise Correlation in Silicon Qubit Devices**

Jun Yoneda<sup>1</sup> (<sup>1</sup>Univ. of Tokyo (Japan))

**15:30 10-02 (Oral 28)**

**Experimental Observation of Sequential Electron Incorporation within P-Donor Molecules in a Silicon Nano-Transistor**

Soumya Chakraborty<sup>1</sup>, Pooja Sudha<sup>1</sup>, Hemant Arora<sup>1</sup>, Daniel Moraru<sup>2</sup>, Arup Samanta<sup>1,3</sup> (<sup>1</sup>Indian Institute of Technology Roorkee, India, <sup>2</sup>Res. Inst. of Electronics, Shizuoka Univ., Japan, <sup>3</sup>Centre of Nanotech., Indian Institute of Technology Roorkee, India)

**15:50 10-03 (Oral 29)**

**Probing Low-Frequency Charge Noise in Few-Hole Physically-Defined Ge Quantum-Dot Single-Hole Transistors**

Chi-Cheng Lai<sup>1</sup>, Ting Tsai<sup>1</sup>, Horng-Chih Lin<sup>1</sup>, Pei-Wen Li<sup>1</sup> (<sup>1</sup>National Yang Ming Chiao Tung University, Taiwan)

**16:10 10-04 (Oral 30)**

**3D Stacked Silicon Quantum Dots Using Potential Barriers by Shared Gates**

Junoh Kim<sup>1</sup>, Daiki Futagi<sup>1</sup>, Tomoko Mizutani<sup>1</sup>, Takuya Saraya<sup>1</sup>, Hiroshi Oka<sup>2</sup>, Takahiro Mori<sup>2</sup>, Masaharu Kobayashi<sup>1,3</sup>, Toshiro Hiramoto<sup>1</sup> (<sup>1</sup>IIS, The Univ. of Tokyo, <sup>2</sup>AIST, <sup>3</sup>d.lab, The Univ. of Tokyo, Japan)

**16:30 10-05 (Oral 31)**

**Multiple-Electron Random Network System Simulation Based on Carbon Nanotube/Polyoxometalate Network**

Shunya Watanabe<sup>1</sup>, Takahide Oya<sup>1</sup> (<sup>1</sup>Yokohama National University, Japan)

**16:50-17:00 Break**

**Session 11: 30<sup>th</sup> Anniversary Panel Session**

**17:00-18:20 Silicon Nanoelectronics and Related Trends Over the Next 30 Years**

Moderator: Daniel Moraru (Shizuoka University)

**18:20-18:30 Closing Remarks (Daniel Moraru & SNW2026 Team)**

## **List of Poster Presentations**

### **P1 Integration of Optimized Superlattice HfO<sub>2</sub>/ZrO<sub>2</sub> Dielectric into High-Performance Superlattice SiGe/Si p-type GAAFETs**

Kai-Ting Huang<sup>1</sup>, Yi-Ju Yao<sup>1</sup>, Heng-Jia Chang<sup>2</sup>, Chen-You Wei<sup>1</sup>, Yu-Min Fu<sup>1</sup>, Bo-Xu Chen<sup>2</sup>, Tsai-Jung Lin<sup>1</sup>, Yung-Teng Fang<sup>2</sup>, Guang-Li Luo<sup>3</sup>, Fu-Ju Hou<sup>3</sup>, Yung-Chun Wu<sup>1,2</sup> (<sup>1</sup>College of Semiconductor Research, <sup>2</sup>Department of Engineering and System Science, National Tsing Hua University, <sup>3</sup>Taiwan Semiconductor Research Institute, Taiwan)

### **P2 BEOL-Compatible GAAFET Hybrid Memory Based on HfO<sub>2</sub>/ZrO<sub>2</sub> Superlattice with Morphotropic Phase Boundary**

Kuei-Chun Liao<sup>1</sup>, Chen-You Wei<sup>1</sup>, Yi-Ju Yao<sup>1</sup>, Cheng-En Wu<sup>2</sup>, Chien-Lung Chen<sup>2</sup>, Chih-Chao Yang<sup>3</sup>, Guang-Li Luo<sup>3</sup>, Fu-Ju Hou<sup>3</sup>, Yung-Chun Wu<sup>1,2</sup> (<sup>1</sup>College of Semiconductor Research, <sup>2</sup>Department of Engineering and System Science, National Tsing Hua University, <sup>3</sup>Taiwan Semiconductor Research Institute, Taiwan)

### **P3 Study on the Application and Reliability of High-k HfO<sub>2</sub>/ZrO<sub>2</sub> Superlattice Dielectrics in Ge Stacked Nanosheet GAAFET at 4K Ultra-Low Temperature**

Kao Tsu-I<sup>1</sup>, Huang Kai-Wei<sup>1</sup>, Wei Chen-You<sup>2</sup>, Lin Yi-Wen<sup>1</sup>, Hou Fu-Ju<sup>3</sup>, Luo Guang-Li<sup>3</sup>, Wu Yung-Chun<sup>1,2</sup> (<sup>1</sup>Dept. of Engineering and System Science, <sup>2</sup>College of Semiconductor Research, National Tsing Hua Univ., Taiwan, <sup>3</sup>Taiwan Semiconductor Research Institute, Taiwan)

### **P4 Enhanced Reliability and Wake-Up Free Behavior of HfO<sub>2</sub>/ZrO<sub>2</sub> Superlattice FeRAM With Triple-Level Cell Using High- and Low-Temperature ALD Stacks**

Kuan-Wen Huang<sup>1</sup>, Kun-Tao Lin<sup>1</sup>, Yu-Yun Wang<sup>1</sup>, Tien-Sheng Chao<sup>1</sup> (<sup>1</sup>Department of Electrophysics, National Yang Ming Chiao Tung University, Taiwan)

### **P5 Implementation of Delay-Enabled Axons for Lightweight Neural Networks with Improving Accuracy in Edge Computing**

GuangJin Li<sup>1,3</sup>, Hao Ai<sup>1,3</sup>, HaoKai Guan<sup>1,3</sup>, LiHao Zhang<sup>1,3</sup>, YuLin Feng<sup>2</sup>, Zheng Zhou<sup>1,3</sup>, Peng Huang<sup>1,3</sup>, LiFeng Liu<sup>1,3</sup> (<sup>1</sup>School of Integrated Circuits, Peking University, China, <sup>2</sup>Beijing Information Science and Technology University, China, <sup>3</sup>Beijing Advanced Innovation Center for Integrated Circuits, China)

### **P6 Study of Single-Photon Detection Using a Back-Gated Si Single-Electron Transistor**

Shogo Miyagawa<sup>1</sup>, Jeygopi Panisilvam<sup>1</sup>, Pooja Sudha<sup>2</sup>, Arup Samanta<sup>2</sup>, Daniel Moraru<sup>1</sup> (<sup>1</sup>Research Institute of Electronics, Shizuoka Univ., Japan, <sup>2</sup>Department of Physics, Indian Institute of Technology Roorkee, India, <sup>3</sup>Centre of Nanotechnology, Indian Institute of Technology Roorkee, India)

### **P7 An Experimental Study on Hot-hole Injection (HHI) in Floating-gate (FG) Flash Memory**



Chang Chen<sup>1</sup>, Yang Feng<sup>1</sup>, Jixuan Wu<sup>1</sup>, Jing Liu<sup>2</sup>, Junyu Zhang<sup>3</sup>, Xuepeng Zhan<sup>1</sup>, Jiezhi Chen<sup>1</sup> (<sup>1</sup>Shandong University, China, <sup>2</sup>Institute of Microelectronics of Chinese Academy of Sciences, China, <sup>3</sup>Neumem Co., Ltd, Hefei, China)

**P8 BEOL-Compatible Annealing Effects on Properties of ALD NbO<sub>x</sub> Films**

Gaoqi Yang<sup>1</sup>, Ruiqing Xie<sup>1</sup>, Linbo Shan<sup>1</sup>, Jiye Li<sup>1</sup>, Zongwei Wang<sup>1,2</sup>, Yimao Cai<sup>1,2</sup> (<sup>1</sup>School of Integrated Circuits, Peking University, China, <sup>2</sup>Beijing Advanced Innovation Center for Integrated Circuits, Peking University, China)

**P9 Multi-Level Split Weight Learning for Multi-Cell ReRAM Computation-in-Memory**

Rei Kusunose<sup>1</sup>, Seiji Adachi<sup>1</sup>, Ayane Matsuzaki<sup>1</sup>, Takao Marukame<sup>1</sup>, Kota Ando<sup>1</sup>, Tetsuya Asai<sup>1</sup> (<sup>1</sup>Graduate School of Information Science and Technology, Hokkaido University, <sup>2</sup>Faculty of Engineering, Hokkaido University, <sup>3</sup>Faculty of Information Science and Technology, Hokkaido University, Japan)

**P10 BEOL-Compatible Microwave Annealing of HfO<sub>2</sub>/ZrO<sub>2</sub> Superlattice Super High-K: Stabilizing Morphotropic Phase Boundaries and Low Leakage Current**

Chen-You Wei<sup>1</sup>, Yu-Hong Chen<sup>2</sup>, Yi-Ju Yao<sup>1</sup>, Guang-Li Luo<sup>3</sup>, Fu-Ju Hou<sup>3</sup>, Yung-Chun Wu<sup>1,2</sup> (<sup>1</sup>College of Semiconductor Research, <sup>2</sup>Department of Engineering and System Science, National Tsing Hua University, <sup>3</sup>Taiwan Semiconductor Research Institute, , Taiwan)

**P11 Design Optimization of SiC CMOS FinFET for High-Temperature Next-generation SoC Logic Applications**

Tae Seong Kwon<sup>1,2</sup>, Young Jo Kim<sup>1</sup>, Hyoung Woo Kim<sup>1</sup>, Young Jun Yoon<sup>3</sup>, Jae Hwa Seo<sup>1</sup>, Sung Yun Woo<sup>2</sup> (<sup>1</sup>Advanced Semiconductor Research Center, Power Semiconductor Research Division, Korea Electrotechnology Research Institute (KERI), <sup>2</sup>School of Electronic and Electrical Engineering, Kyungpook National University, <sup>3</sup>School of Electronics and Mechanical Engineering, Gyeongbuk National University, Korea)

**P12 XNOR Logic Implementation Using a Single Steep-Switching Positive Feedback Device**

Jisung Im<sup>1</sup>, Hansol Kim<sup>1</sup>, Hojin Moon<sup>1</sup>, Eunjeong Jang<sup>1</sup>, Jong-Ho Bae<sup>2</sup>, Sung Yun Woo<sup>1</sup> (<sup>1</sup>School of EE, Kyungpook National University, <sup>2</sup>School of SSE, Yonsei University, Korea)

**P13 Reliability Characterizations on the Hybrid Hot-Cold Data Conversion in 3D NAND Flash Memory under Various Temperatures**

Yujiao Ding<sup>1</sup>, Ruidong Li<sup>2</sup>, Yining Zhou<sup>1</sup>, Xinghao Wang<sup>1</sup>, Peng Guo<sup>3</sup>, Yixuan Fan<sup>1</sup>, Pengpeng Sang<sup>1</sup>, Jixuan Wu<sup>1</sup>, Xuepeng Zhan<sup>1</sup>, Jiezhi Chen<sup>1</sup> (<sup>1</sup>Shandong Univ., China, <sup>2</sup>Cloud Computing Equipment Industry Innovation Co., Ltd., China, <sup>3</sup>Shandong Sinochip Semiconductors Co. Ltd., Jinan, China)

**P14 Synaptic Emulated by Double-layer ZnO Resistive RAM (ReRAM) via Optimized Sputter and Low-temperature ALD Process**

Xuepeng Zhan<sup>1</sup>, Junyao Mei<sup>1</sup>, Yuzhe Hu<sup>1</sup>, Yifan Wu<sup>1</sup>, Hongyang Zhang<sup>1</sup>, Pengpeng Sang<sup>1</sup>, Jixuan Wu<sup>1</sup>, Jiezhi Chen<sup>1</sup> (<sup>1</sup> University, China, <sup>2</sup>Cloud Computing Equipment Industry Innovation Co., Ltd., Jinan, China, <sup>3</sup>Shandong Sinochip Semiconductors Co. Ltd, Jinan, China)

**P15 Flash-based Computing-in-Memory (CiM) Architectures for High-accuracy Classification**

Yixuan Fan<sup>1</sup>, Yang Feng<sup>1</sup>, Jixuan Wu<sup>1</sup>, Jing Liu<sup>2</sup>, Junyu Zhang<sup>3</sup>, Zhi Liu<sup>1</sup>, Xuepeng Zhan<sup>1</sup>, Jiezhi Chen<sup>1</sup> (<sup>1</sup>Shandong University, China, <sup>2</sup>Key Laboratory of Microelectronic Devices and Integrated Technology, Institute of Microelectronics of Chinese Academy of Sciences, China, <sup>3</sup>Neumem Co., Ltd, Hefei, China)

**P16 Learning with Fewer States: A Robust On-Chip Learning Algorithm Resilient to Conductance State Constraints in RRAM-based Neural Networks**

Zhixing Cai<sup>1</sup>, Jingwei Sun<sup>1</sup>, Zongwei Wang<sup>1</sup>, Zhizhen Yu<sup>1</sup>, Ruiqing Xie<sup>1</sup>, Zezhi Cheng<sup>1</sup>, Lin Bao<sup>1</sup>, Zheng Zhou<sup>1</sup>, Ling Liang<sup>1</sup>, Yimao Cai<sup>1</sup> (<sup>1</sup>School of Integrated Circuits, Peking University, China, <sup>2</sup>Beijing Advanced Innovation Center for Integrated Circuits, Peking University, China)

**P17 Experimental Study on Double-layer ZnO Resistive RAM (ReRAM) by Co-optimized Sputtering and Low-temperature ALD Processes**

Junyao Mei<sup>1</sup>, Ruidong Li<sup>2</sup>, Yifang Wu<sup>1</sup>, Di Wu<sup>1</sup>, Bo Chen<sup>1</sup>, Peng Guo<sup>3</sup>, Pengpeng Sang<sup>1</sup>, Jixuan Wu<sup>1</sup>, Xuepeng Zhan<sup>1</sup>, Jiezhi Chen<sup>1</sup> (<sup>1</sup>Shandong University, China, <sup>2</sup>Cloud Computing Equipment Industry Innovation Co., Ltd., China, <sup>3</sup>Shandong Sinochip Semiconductors Co. Ltd., Jinan, China)

**P18 Reliability Analysis of CFETs Under Various NBTI Conditions**

Hsiang-Ting Kung<sup>1</sup>, Narasimhulu Thoti<sup>2</sup>, Hannu-Pekka Komsa<sup>2</sup>, Ying-Tsan Tang<sup>1</sup> (<sup>1</sup>National Central University, Taiwan, <sup>2</sup>University of Oulu, Finland)

**P19 A Ballistic Transport Model for Nanosheet CFETs with Si(100), (110), and (111) Channel Orientations**

Yung-Chin Yang<sup>1</sup>, Hung-Ming Tsai<sup>1</sup>, Te-Kung Chiang<sup>2</sup>, and Yeong-Her Wang<sup>1\*</sup> (<sup>1</sup>National Cheng-Kung University, Taiwan, <sup>2</sup>National University of Kaohsiung, Taiwan)

**P20 Quantitative Analysis of Endurance–dependent Charge Trapping Dynamics in Ferroelectric Field–Effect Transistors with Temperature Effects**

Hyojin Yang<sup>1</sup>, Haesung Kim<sup>1</sup>, Changhyeon Han<sup>3</sup>, Yoon Jung Lee<sup>1</sup>, Sung-Jin Choi<sup>1</sup>, Dae Hwan Kim<sup>1</sup>, Dong Myong Kim<sup>4</sup>, Daewoong Kwon<sup>3</sup>, Jong-Ho Bae<sup>2</sup> (<sup>1</sup>Kookmin University, Korea, <sup>2</sup>Hanyang University, Korea, <sup>3</sup>DGIST, Korea, <sup>4</sup>Yonsei University, Korea)

**P21 Analysis of Grain Boundary Effects Based on Location in a Diode-Type NAND Flash Memory Cell**

Jinsu Kim<sup>1</sup>, Hansol Kim<sup>2</sup>, Hojin Moon<sup>2</sup>, Wonjun Song<sup>2</sup>, Jong-Ho Bae<sup>3</sup>, Nagyong Choi<sup>4</sup>, Sung Yun Woo<sup>1,2</sup> (<sup>1</sup>School of SCE, Kyungpook National University, Korea, <sup>2</sup>School of EEE, Kyungpook National University, Korea, <sup>3</sup>Dept. of SSE, Yonsei University, <sup>4</sup>Dept. of ECE, Seoul National University, Korea)

**P22 Evaluation of In-Memory Logic Computation for Ferroelectric Capacitive Memory**

Hao-Hsiang Chang<sup>1</sup>, Po-Tsang Huang<sup>1</sup>, Pin Su<sup>1</sup> (<sup>1</sup>Institute of Pioneer Semiconductor Innovation, <sup>2</sup>International College of Semiconductor Technology, <sup>3</sup>Institute of Electronics, National Yang Ming Chiao Tung University, Taiwan)

**P23 Volatile and Nonvolatile Resistive Switching in Wafer-Scale MoS<sub>2</sub> Memristors**

Yuan Fa<sup>1,2</sup>, Dennis Braun<sup>2</sup>, Lukas Völkel<sup>2</sup>, Holger Lerch<sup>1</sup>, Holger Kalisch<sup>2</sup>, Michael Heuken<sup>2,3</sup>, Andrei Vescan<sup>2</sup>, Zhenxing Wang<sup>1</sup>, Max C. Lemme<sup>1,2</sup> (<sup>1</sup>AMO GmbH, Advanced Microelectronic Center Aachen, Germany, <sup>2</sup>RWTH Aachen University, Germany, <sup>3</sup>AIXTRON SE, Germany)

**P24 Impact of Oxygen Vacancies on Switching Behavior of Ferroelectric HfO<sub>2</sub> from First Principle**

Chenxi Yu<sup>1</sup>, Xujin Song<sup>1</sup>, Jiajia Zhang<sup>1</sup>, Dijiang Sun<sup>1</sup>, Xiaoyan Liu<sup>1</sup>, Fei Liu<sup>1</sup>, Jinfeng Kang<sup>1</sup> (<sup>1</sup>School of Integrated Circuits, Peking University, China)

**P25 Tunable Tunnel Coupling in Vertically Stacked Symmetric FinFET-Based Ge Double Quantum Dots**

Hua Yang<sup>1</sup>, Wei-Yuan Lai<sup>1</sup>, Ying-tsan Ethan Tang<sup>1</sup> (<sup>1</sup>National Central University, Taiwan)

**P26 Numerical Investigation of Electrical Performance and Scaling Properties in 6T1C IGZO-Based Synaptic Devices**

Ye-Han Kwon<sup>1</sup>, Youngchae Roh<sup>2</sup>, Changhoon Joe<sup>2</sup>, Sangbum Kim<sup>2</sup>, Sung-Min Hong<sup>1</sup> (<sup>1</sup>Gwangju Institute of Science and Technology, Korea, <sup>2</sup>Seoul National University, Korea)

**P27 Investigation of Asymmetric Ferroelectric Switching in AlScN MFM Capacitors**

Hirofumi Nishida<sup>1</sup>, Si-Meng Chen<sup>1</sup>, Takuya Hoshii<sup>1</sup>, Kazuo Tsutsui<sup>1</sup>, Hitoshi Wakabayashi<sup>1</sup>, Kuniyuki Kakushima<sup>1</sup> (<sup>1</sup>Institute of Science Tokyo, Japan)

**P28 Phosphorus Incorporation and Ionization in Ultra-Thin Silicon Films**

Andrea Pulici<sup>1,2</sup>, Gabriele Seguini<sup>1</sup>, Marco Fanciulli<sup>2</sup>, Michele Perego<sup>1</sup> (<sup>1</sup>CNR-IMM, Unit of Agrate Brianza, Italy, <sup>2</sup>Università degli Studi di Milano-Bicocca, Italy)

**P29 All-in-one Monolithic 3D Heterostructured Integration of BEOL-Complementary N-Si FinFET / P-CNFET for Smart Edge Processing**

Shuang Liu<sup>1,2</sup>, Feixiong Wang<sup>1,2</sup>, Heyi Huang<sup>1,2</sup>, Yadong Zhang<sup>1,2</sup>, Yanqing Li<sup>1,2</sup>, Yanzhao Wei<sup>1,2</sup>, Huaxiang Yin<sup>1,2</sup> (<sup>1</sup>Institute of Microelectronics of the Chinese Academy of Sciences, Beijing, <sup>2</sup>School of Integrated Circuits, University of Chinese Academy of Sciences, Beijing, China)

**P30 Machine Learning-Driven Modeling for Fast and Accurate Z-Interference Estimation in 3D NAND Scaling**

Hyeon Seo Yun<sup>1</sup>, Jong Kyung Park<sup>1</sup> (<sup>1</sup>Seoul National University of Science and Technology, Korea)

**P31 The Impacts of Different Producing Methods on the Memristive Performance in Monolayer CBRAM**

Xuepeng Zhan<sup>1</sup>, Yuwei Qu<sup>1</sup>, Hongyang Zhang<sup>1</sup>, Yifan Wu<sup>1</sup>, Di Wu<sup>1</sup>, Bo Chen<sup>1</sup>, Yixuan Fan<sup>1</sup>, Pengpeng Sang<sup>1</sup>, Jixuan Wu<sup>1</sup>, Jiezhi Chen<sup>1</sup> (<sup>1</sup>Shandong University, Qingdao, China, <sup>2</sup>Cloud Computing Equipment Industry Innovation Co., Ltd., Jinan, China, <sup>3</sup>Shandong Sinochip Semiconductors Co. Ltd, Jinan, China)

**P32 Displacement Damage Effects Induced by Proton Irradiation in  $\beta$ -Ga<sub>2</sub>O<sub>3</sub> Schottky Barrier Diodes**

Youngjo Kim<sup>1</sup>, Tae Seong Kwon<sup>2,1</sup>, Sung Yun Woo<sup>2</sup>, Young Jun Yoon<sup>3</sup>, Jae Hwa Seo<sup>1</sup> (<sup>1</sup>Korea Electrotechnology Research Institute (KERI), Korea, <sup>2</sup>Kyungpook National University, Korea, <sup>3</sup>Gyeongbuk National University, Korea)

**P33 Determination of sensitivity limits for single molecule detection using single-electron sensing devices**

Alexei O. Orlov<sup>1</sup>, Istiaque Rahaman<sup>1</sup>, Gergo P. Szakmany<sup>1</sup>, Gregory L. Snider<sup>1</sup> (<sup>1</sup>Department of Electrical Engineering, University of Notre Dame, USA)